

Physics of Nanoscale Transistors

Mark Lundstrom
Electrical and Computer Engineering
Purdue University, West Lafayette, IN

1. Introduction
2. The Ballistic MOSFET
3. Scattering Theory of the MOSFET
4. Beyond the Si MOSFET
5. Summary

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additional information at: www.ece.purdue.edu/celab



Acknowledgements

collaborators:

Professor Supriyo Datta, Jing Guo, Sayed Hasan, Zhibin Ren,
Jung-Hoon Rhew, Anisur Rahman, Ramesh Venugopal,
Jing Wang

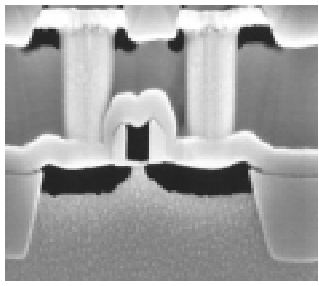
sponsors: NSF, SRC

MARCO Focus Center on Materials, Devices Structures
ARO DURINT
Indiana 21st Century Research and Technology Fund


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1. Introduction

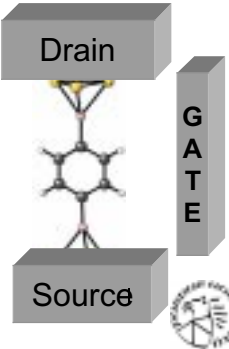


MOSFET



CNTFET
Bachtold, et al.,
Science, Nov. 2001

Molecular FETs?



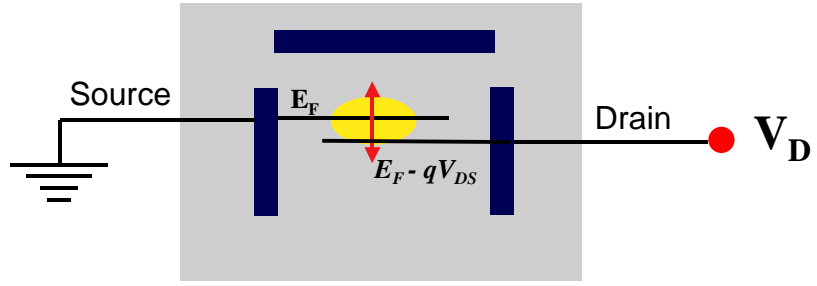
Drain

Source

GATE

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1. Introduction



Gate

Source

Drain V_D

E_F

$E_F - qV_{DS}$

- 1) self-consistent electrostatics
- 2) transport

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1. Introduction

$$Q = C_{GS} V_{GS} + C_{DS} V_{DS}$$
 (electrostatics)

$$Q = Q^+(E_F) + Q^-(E_F - qV_{DS})$$

$$I_D = I^+(E_F) - I^-(E_F - qV_{DS})$$

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1. Introduction

$$Q(x)$$

at $x = 0 \dots$

$$Q(0) \approx C_{GS} V_{GS} + C_{GD} V_{GD}$$

$$C_{GS} \approx C_{ox} \quad (\text{constant})$$

$$C_{DS} \ll C_{GS}$$

$$\rightarrow Q(0) \approx C_{ox} (V_{GS} - V_T)$$

1) Compute $Q(V_{GS}, V_{DS})$ 2) Determine E_F 3) Compute I_D

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1. Introduction

Now.....

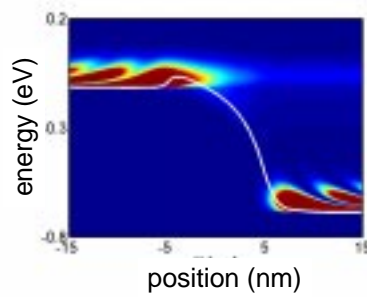
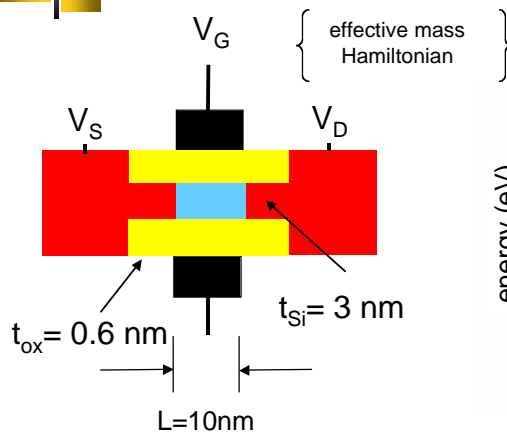
let's see how these ideas work out for MOSFETs

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1. Introduction

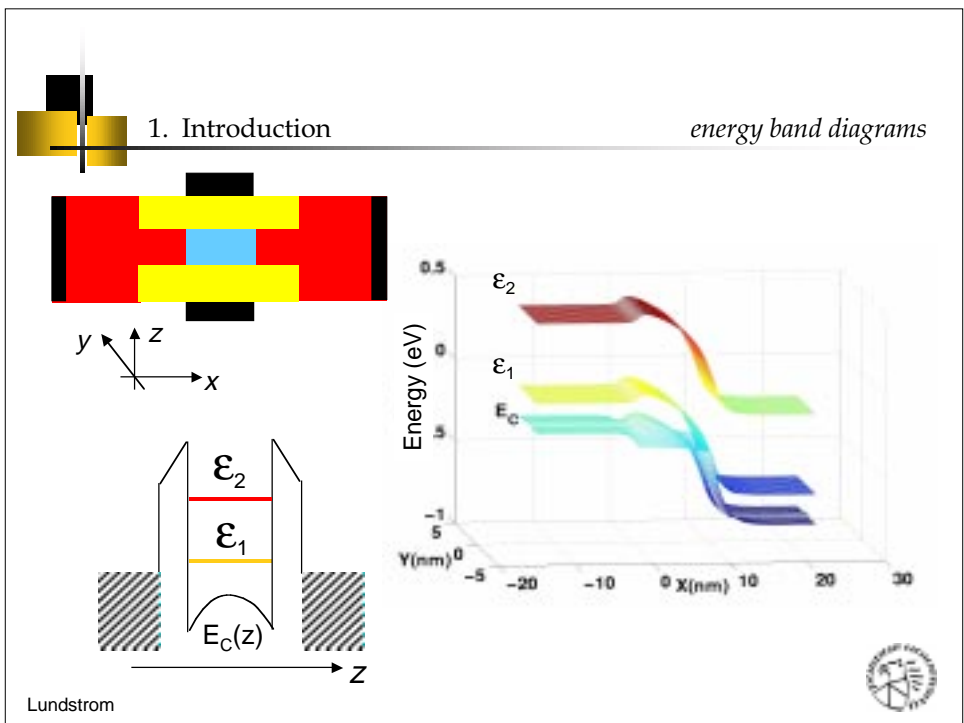
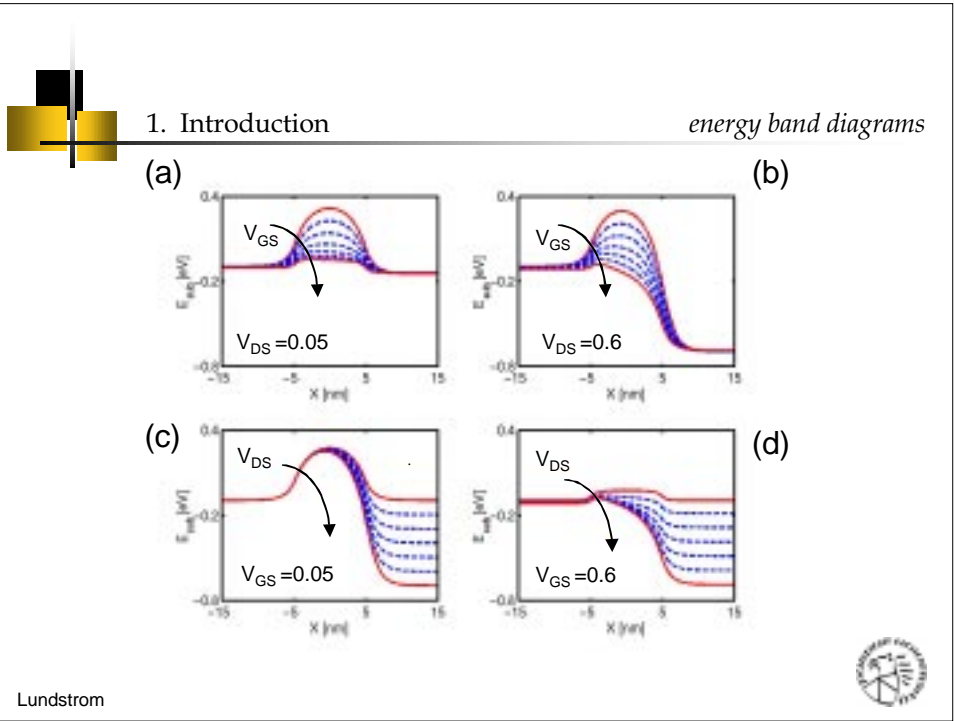
nanoMOS simulations



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Z. Ren, R. Venugopal, S. Datta, and M. Lundstrom, IEDM, 2001

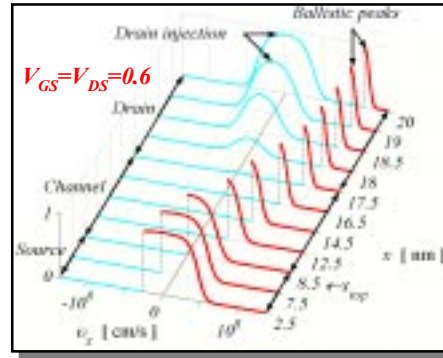
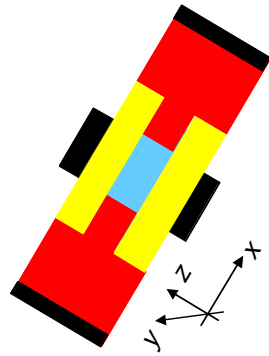






1. Introduction

transport



- 2D Electrostatics
- Strong off-equilibrium transport
- Scattering

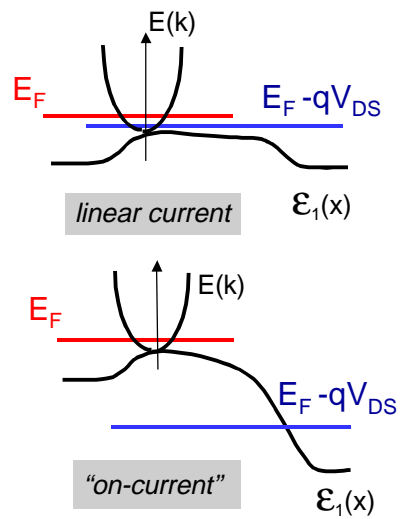
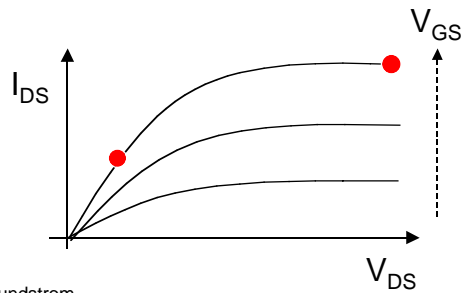
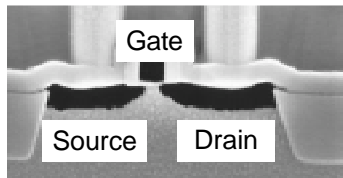


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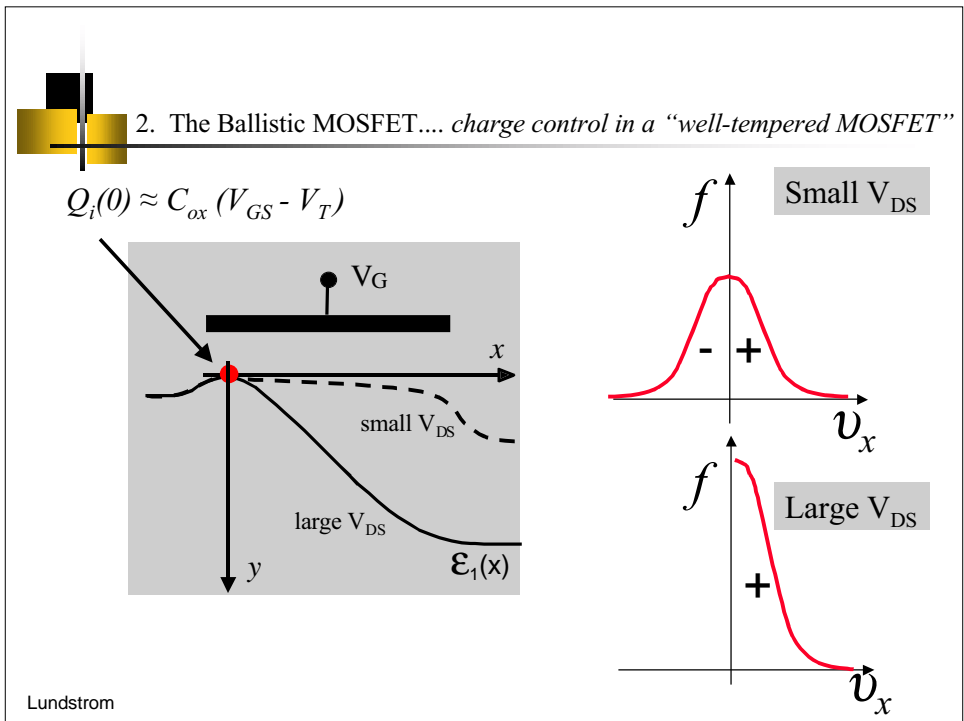
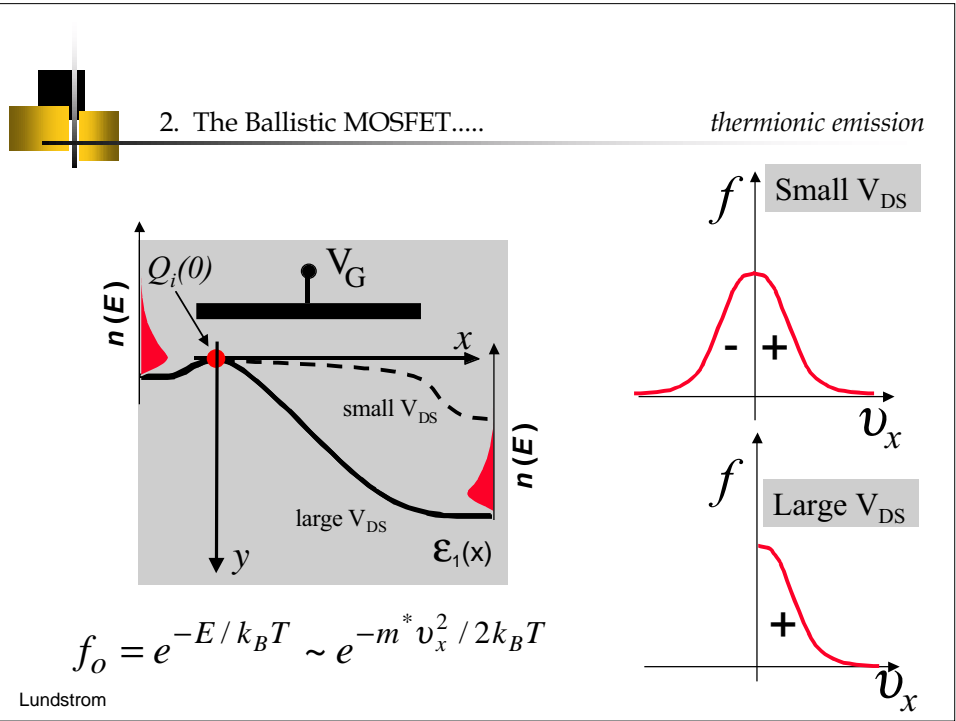


2. The Ballistic MOSFET

Natori's theory



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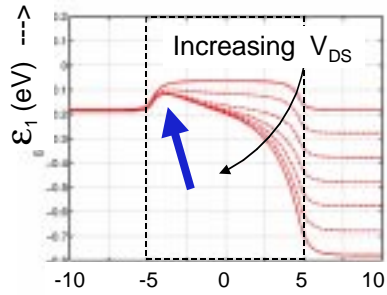




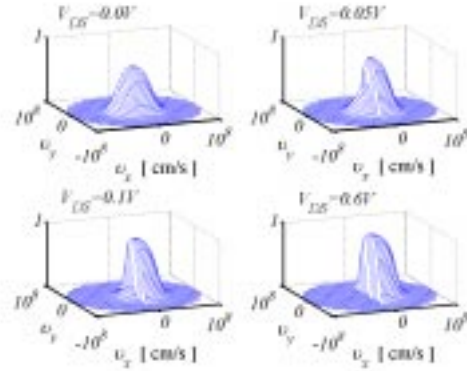
2. The Ballistic MOSFET.....

numerical solution of the ballistic BTE

ϵ_1 vs. x for $V_{GS} = 0.5V$



$f(k_x, k_y)$



J.-H. Rhew, Purdue University



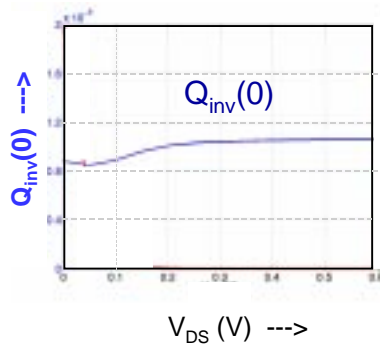
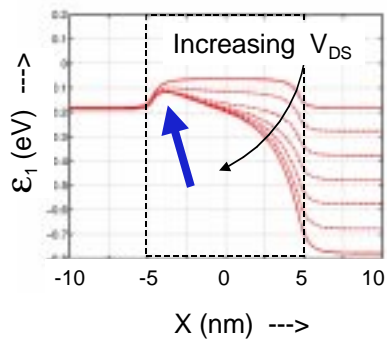
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2. The Ballistic MOSFET.....

charge control

ϵ_1 vs. x for $V_{GS} = 0.5V$



i) $Q_i(0) \approx \text{constant}$

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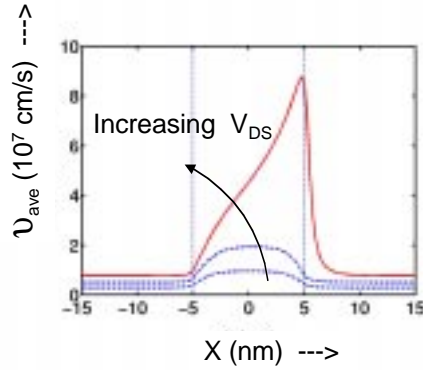
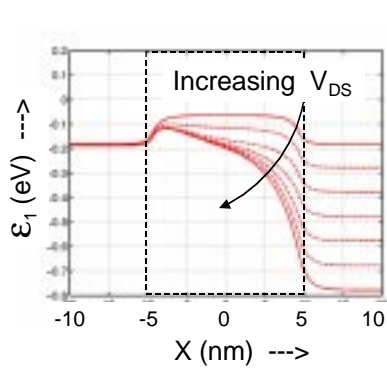




2. The Ballistic MOSFET.....

ϵ_1 vs. x for $V_{GS} = 0.5V$

- i) $Q_i(0) \approx \text{constant}$
- ii) $\langle v(0) \rangle \rightarrow v_T$



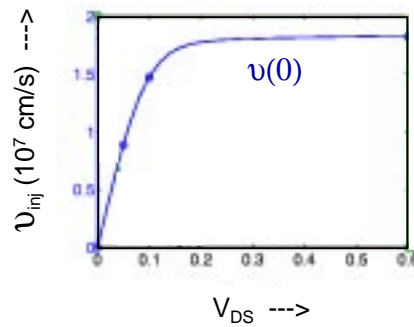
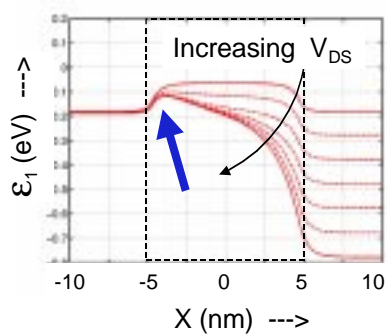
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2. The Ballistic MOSFET..... *velocity saturation* in a ballistic FET

ϵ_1 vs. x for $V_{GS} = 0.5V$

- i) $Q_i(0) \approx \text{constant}$
- ii) $\langle v(0) \rangle \rightarrow v_T$



$v(0) \rightarrow \tilde{v}_T$

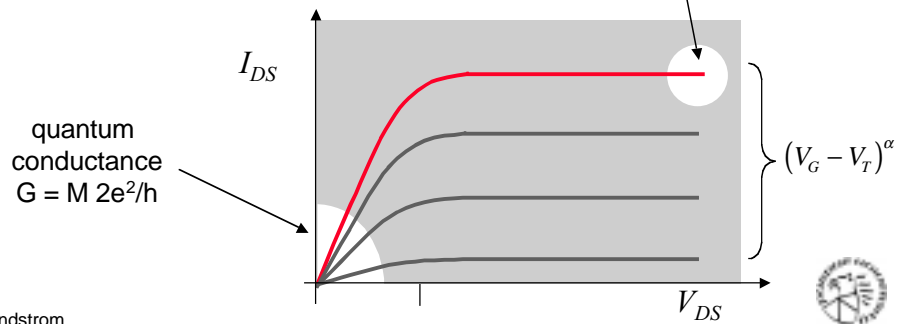
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2. The Ballistic MOSFET.....

$$I_{DS} = W Q_i(V_{GS}) \tilde{v}_T \times \left\{ \frac{1 - \frac{F_{1/2}(\eta_F - U_{DS})}{F_{1/2}(\eta_F)}}{1 + \frac{F_0(\eta_F - U_{DS})}{F_0(\eta_F)}} \right\} \quad I_{DS(on)} = W C_{ox} \tilde{v}_T (V_{GS} - V_T)$$



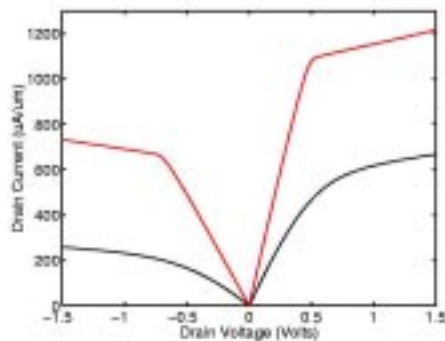
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2. The Ballistic MOSFET.....

comparison with measurements.....

$L_{eff} = 115/125$ nm technology



— measured
— ballistic (with measured R_s)

NMOS: ~ 50% of limit

PMOS: ~ 33% of limit

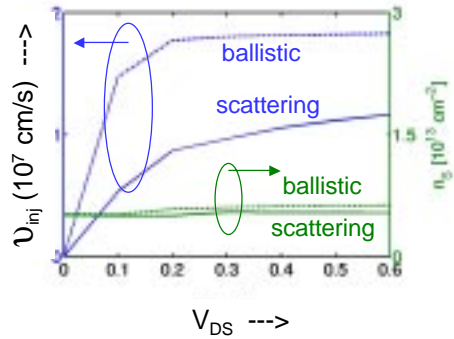
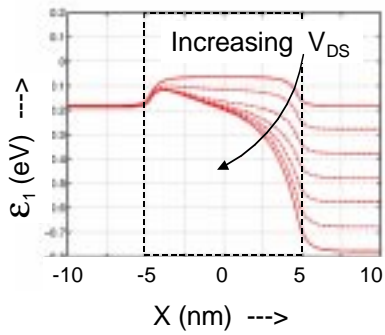
- F. Assad, et al. (1999 IEDM)
- G. Timp, J. Bude, et al., (1999 IEDM)
- D. Rumsey (TECHON 2000)
- A. Lochtefeld, D. Antoniadis (EDL, Feb 2001)

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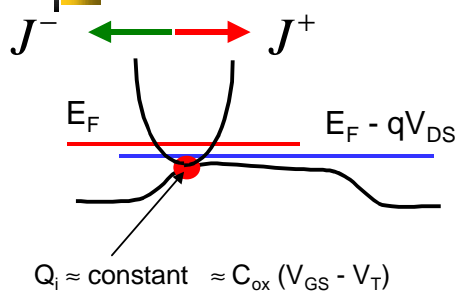
3. Scattering Theory of the MOSFET.....



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3. Scattering Theory of the MOSFET.....



$$J^+ = n^+ \tilde{v}_T^+$$

$$J^- = (1 - T)J^+ + TJ_{ball}^-$$

$$I_D = Wq(J^+ - J^-)$$

$$Q_i(V_{GS}) = \frac{q(J^+ + J^-)}{\tilde{v}_T^+}$$

$$I_{DS} = WQ_i(V_{GS})\tilde{v}_T^+ \left(\frac{T}{2-T} \right) \times \left\{ \frac{1 - \frac{F_{1/2}(\eta_F - U_{DS})}{F_{1/2}(\eta_F)}}{1 + \left(\frac{T}{2-T} \right) \frac{F_0(\eta_F - U_{DS})}{F_0(\eta_F)}} \right\}$$

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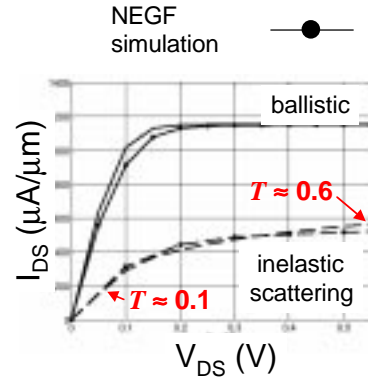
3. Scattering Theory of the MOSFET.....

Landauer/McKelvey model

$$I_{DS} = WC_{ox}(V_{GS} - V_T)\tilde{v}_T\left(\frac{T}{2-T}\right) \times$$

$$\frac{F_{1/2}(\eta_F)}{\ln(1+e^{\eta_F})} \times \left\{ \frac{1 - \frac{F_{1/2}(\eta_F - U_{DS})}{F_{1/2}(\eta_F)}}{1 + \left(\frac{T}{2-T}\right) \frac{\ln(1+e^{\eta_F - U_{DS}})}{\ln(1+e^{\eta_F})}} \right\}$$

$$T(V_{GS}, V_{DS})$$

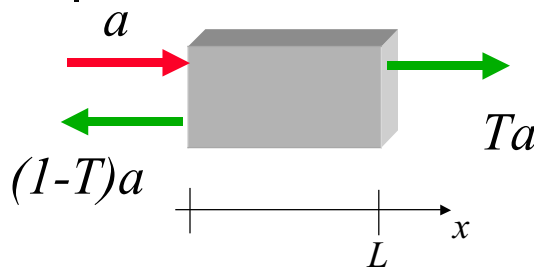


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3. Scattering Theory of the MOSFET.....

computing T : low V_{DS}



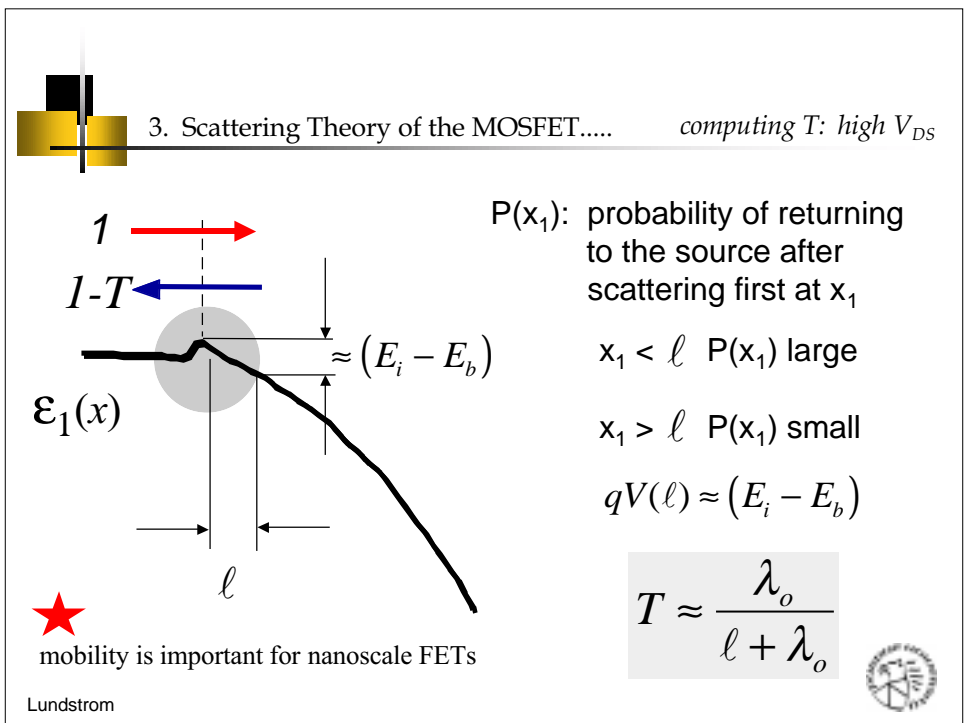
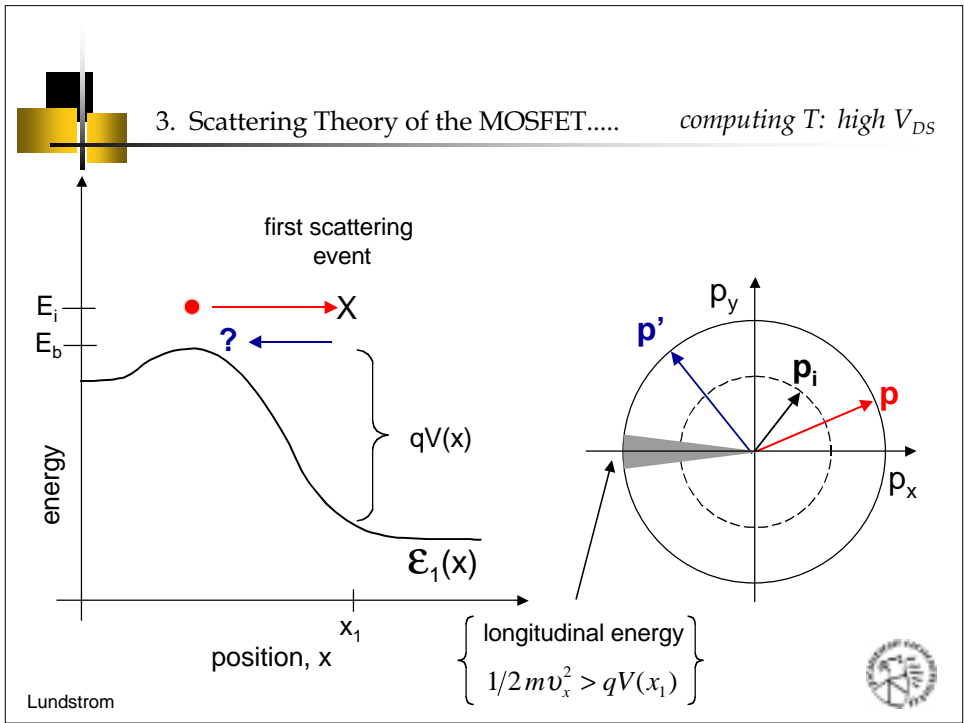
$$T = \frac{\lambda_0}{L + \lambda_0}$$

$$I_{DS} = WC_{ox} \left(\frac{v_T}{k_B T / q} \right) T (V_{GS} - V_T) V_{DS}$$

$$I_{DS} = \mu_{eff} C_{ox} \left(\frac{W}{L + \lambda_0} \right) (V_{GS} - V_T) V_{DS}$$

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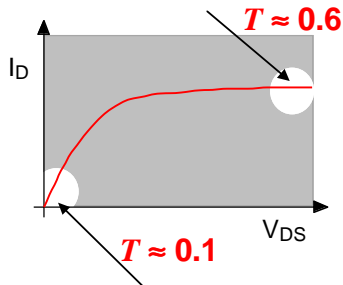






3. Scattering Theory of the MOSFET..... Landauer/McKelvey model

$$I_D = W C_{ox} v_T \left(\frac{T}{2-T} \right) (V_{GS} - V_T)$$



$$I_D = W C_{ox} \left(\frac{v_T / 2}{k_B T / q} \right) T (V_{GS} - V_T) V_{DS}$$

$$I_{DS} = W C_{ox} (V_{GS} - V_T) \tilde{v}_T \left(\frac{T}{2-T} \right) \times$$

$$\left[\frac{1 - \frac{F_{1/2}(\eta_F - U_{DS})}{F_{1/2}(\eta_F)}}{1 + \left(\frac{T}{2-T} \right) \frac{\ln(1 + e^{\eta_F - U_{DS}})}{\ln(1 + e^{\eta_F})}} \right]$$

$$T = \frac{\lambda_o}{\ell + \lambda_o}$$



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- transmission theory provides a clear picture of MOSFETs at the scaling limit:

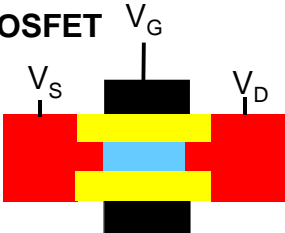
- source velocity is limited by thermal injection
- velocity saturation occurs at the source
- the scattering that matters occurs near the source
- "mobility" is relevant to nanoscale MOSFETs



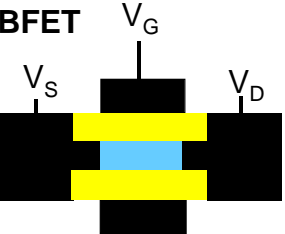
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4. Beyond the Si MOSFET.....

1) MOSFET




2) SBFET



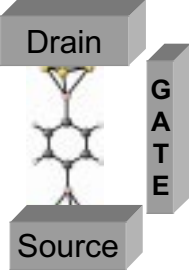

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3) CNTFET



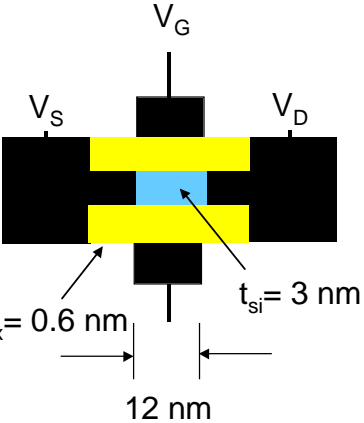
Bachtold, et al.,
Science, Nov.
2001

4) Molecular FETs?

4. Beyond the Si MOSFET.....

the Schottky barrier MOSFET



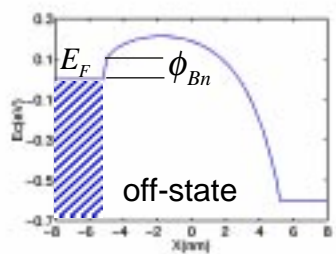
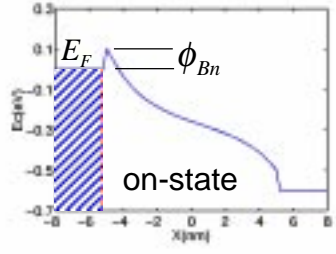
$t_{ox} = 0.6 \text{ nm}$

$t_{si} = 3 \text{ nm}$

12 nm

Jing Guo (Purdue)

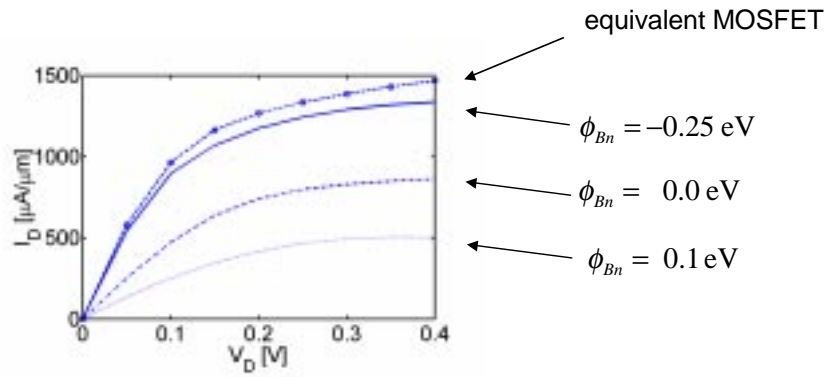
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4. Beyond the Si MOSFET.....

the Schottky barrier MOSFET

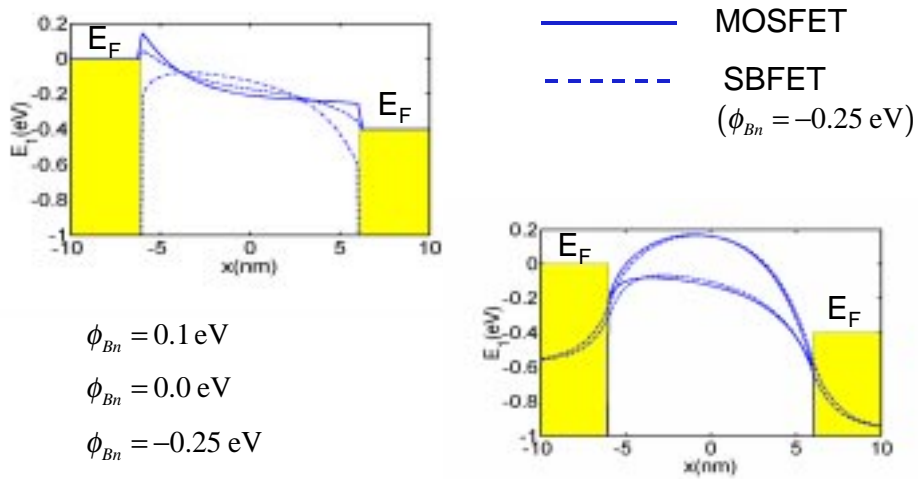


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4. Beyond the Si MOSFET.....

the Schottky barrier MOSFET



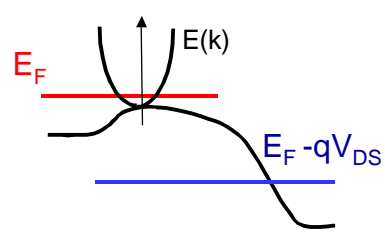
Lundstrom



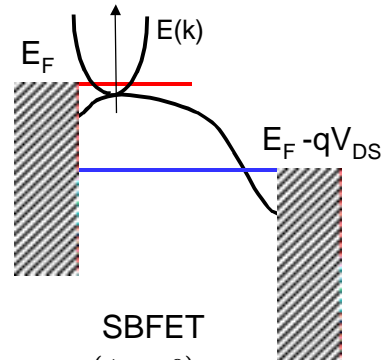


4. Beyond the Si MOSFET.....

the Schottky barrier MOSFET



MOSFET



SBFET
($\phi_{Bn} < 0$)

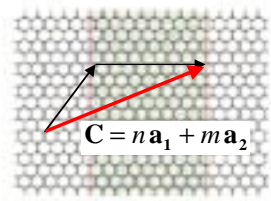
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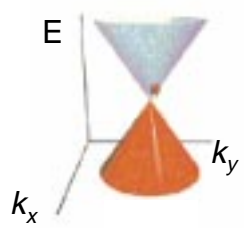
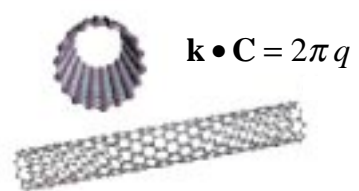
4. Beyond the Si MOSFET.....

the CNTFET

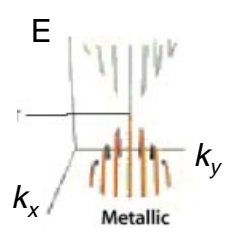
graphene



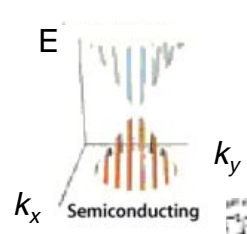
(n, m) carbon nanotube



(n-m) = multiple of 3

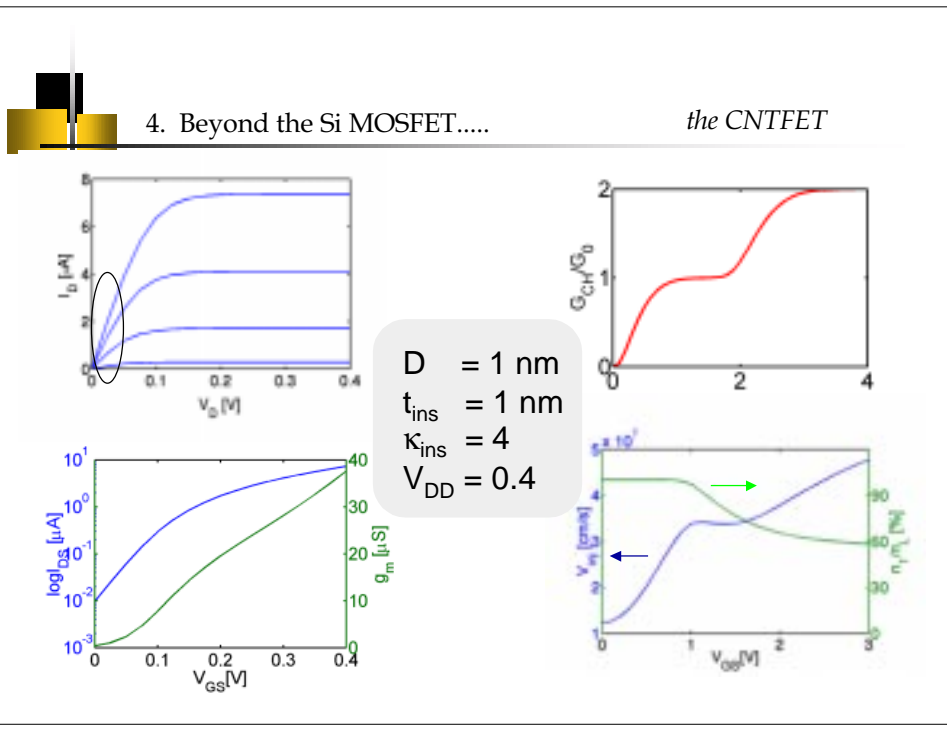
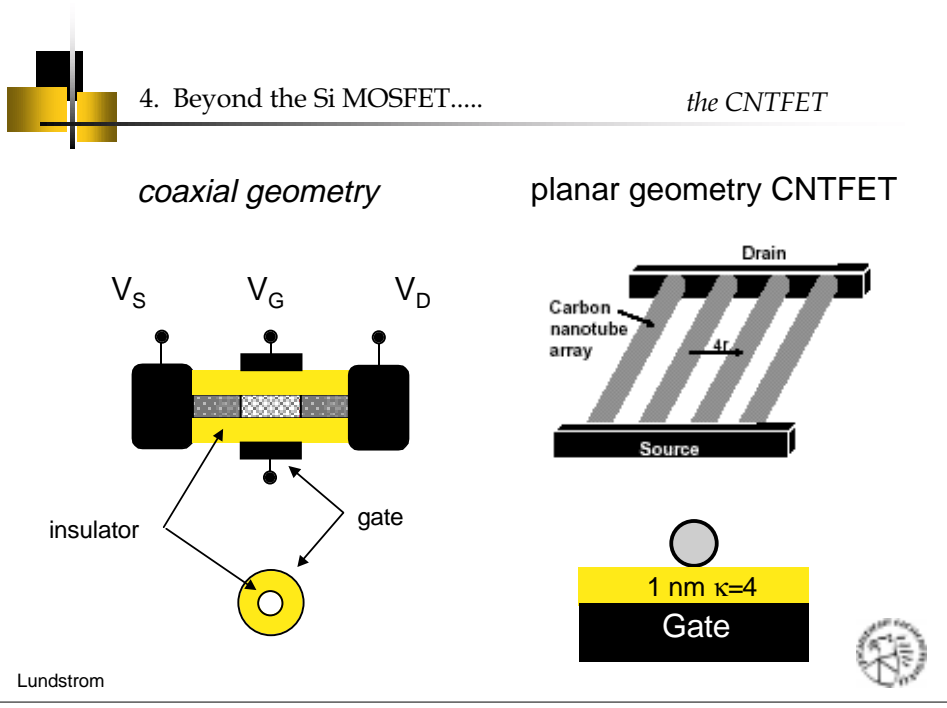


(n-m) ≠ multiple of 3



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5. Summary

- Essential physics of nanoscale transistors is controlled by:
 - electrostatics*
 - state filling*
 - transmission*
- Transmission theory provides insights into nanoscale MOSFET physics
 - velocity saturation at the source
 - importance of scattering near the source
 - relevance of mobility
- The performance of transistors based on charge control is largely material-independent

